ABSTRACT OF THE DISCLOSURE

A method for creating charged-particle-beam
exposure data containing a description of an exposure
sequence of character patterns to perform exposure of
5   a charged-particle-beam according to a character
projection technique, comprising selecting first or
second values as a parameter to transfer one character
pattern and then transferring a subsequent character
pattern, the first value regarding performance of a
10   shaping deflector which deflects the charged particle
beam so that the charged particle beam is applied to an
arbitrarily character aperture formed in a CP aperture
mask and a character beam having the shape of the
character aperture is thereby created, and the second
15   value regarding performance of an objective deflector
which deflects the character beam so that the character
beam is applied to an arbitrarily position of the
deflection region of the specimen, and determining the
exposure sequence of the character patterns in the
20   deflection region in accordance with the selected
parameter.